

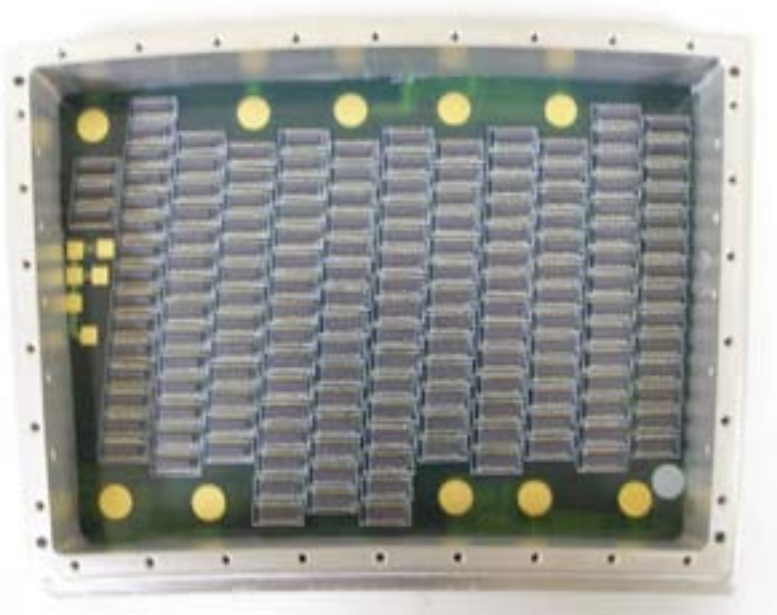
Asian Module R&D Status & Plan

**Akira Sugiyama(Saga)
on behalf of LCTPC-Asia/Japan**

Conceptual design of our module

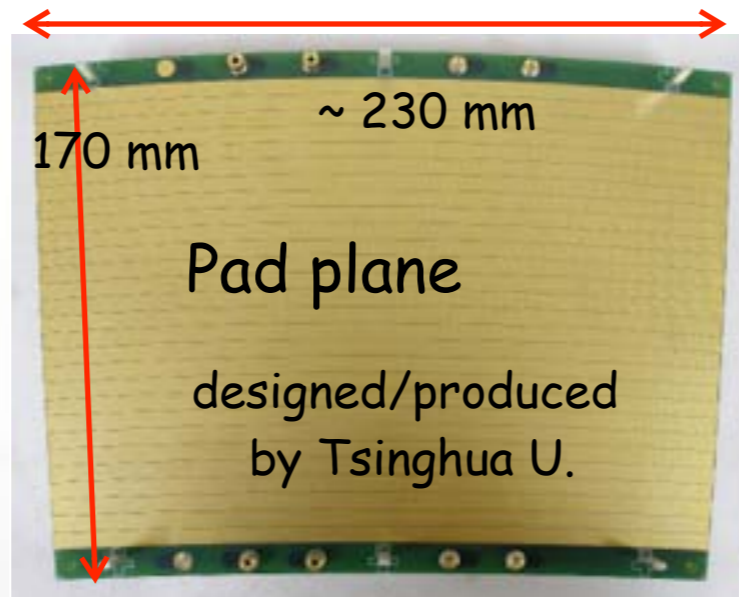
Minimize insensitive regions(module boundary, GEM frame)
pointing IP

no side frame



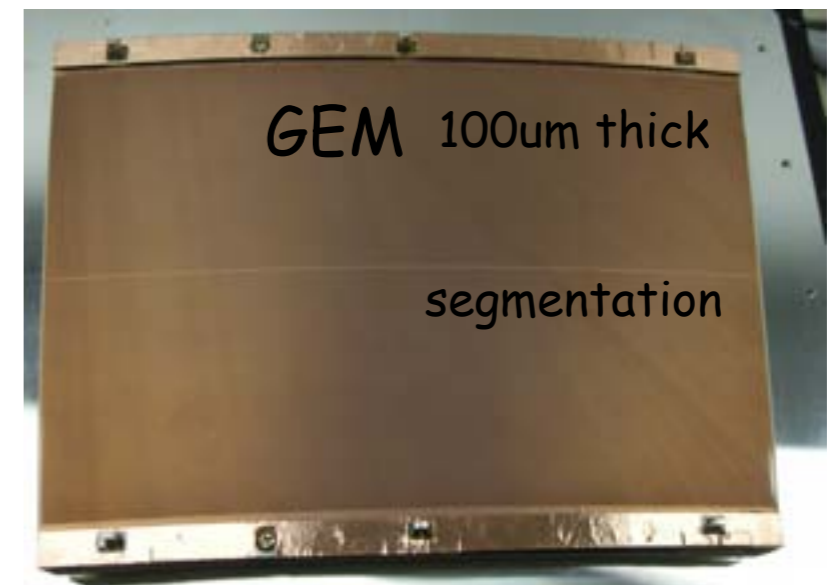
Bunch of tiny connectors
(40 pins) 161 connectors

all other space for HV supply
+ Back Frame



28 pad rows (176/192 pads/raw)
~1.2(w) x 5.4(h) mm²
staggered every each layer

Total 5,152 ch/module



Double GEM (100um thick)
for simpler structure

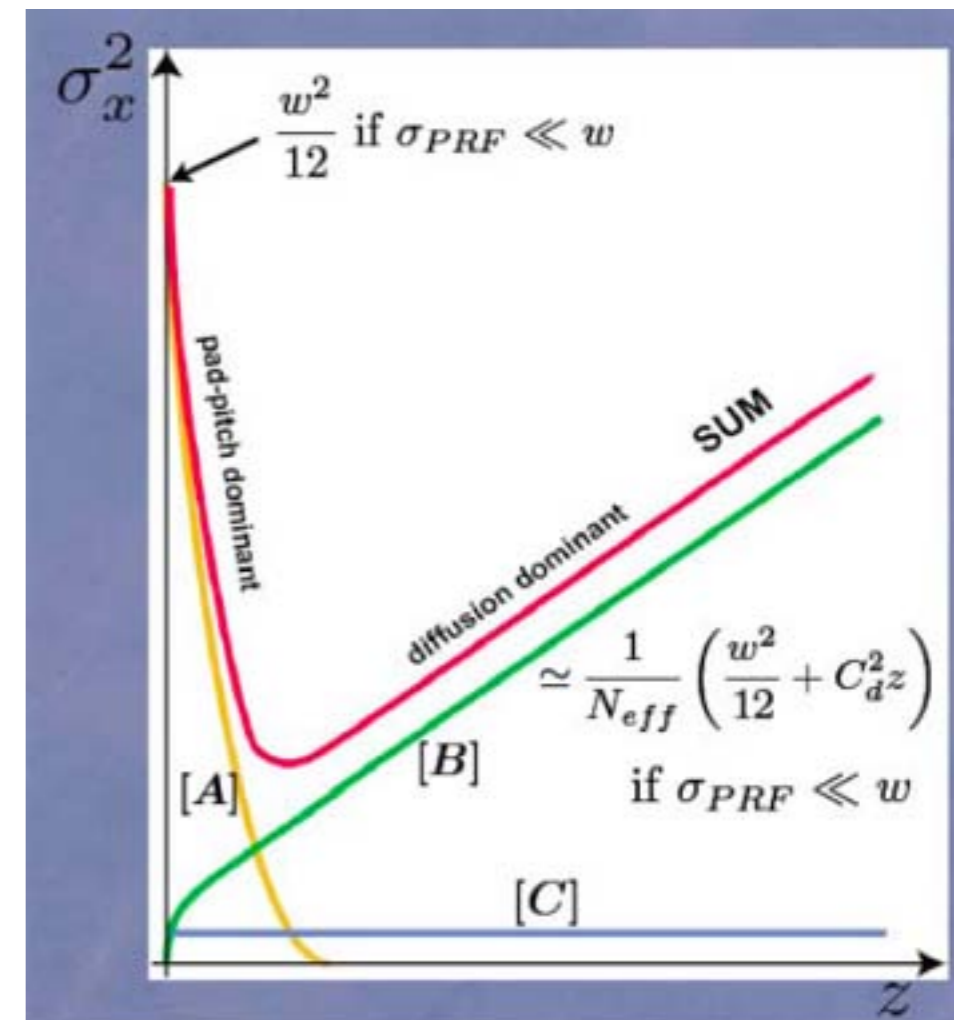
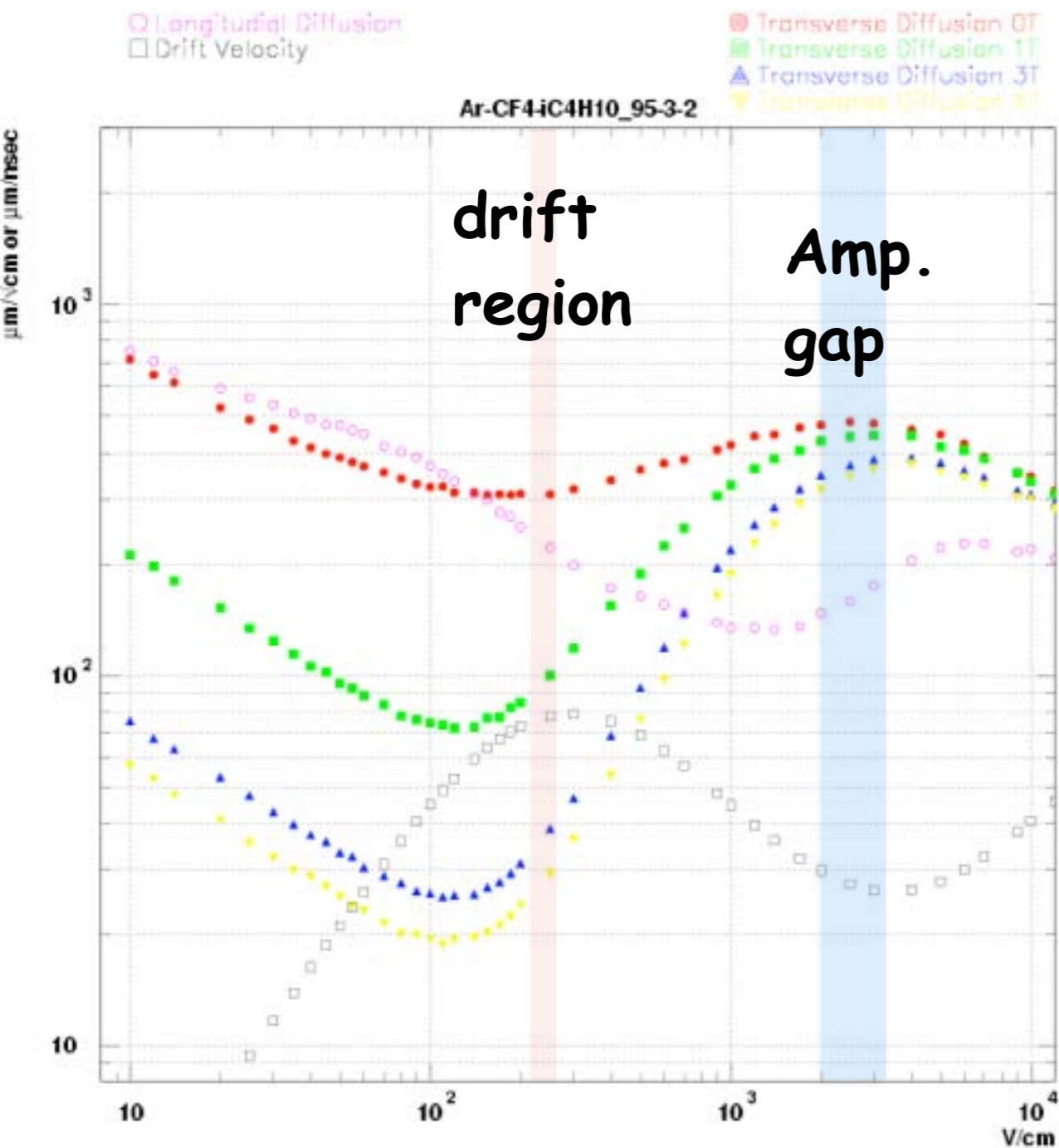
GEM electrode is divided in the
middle of R

Gate GEM is assumed above GEM structure

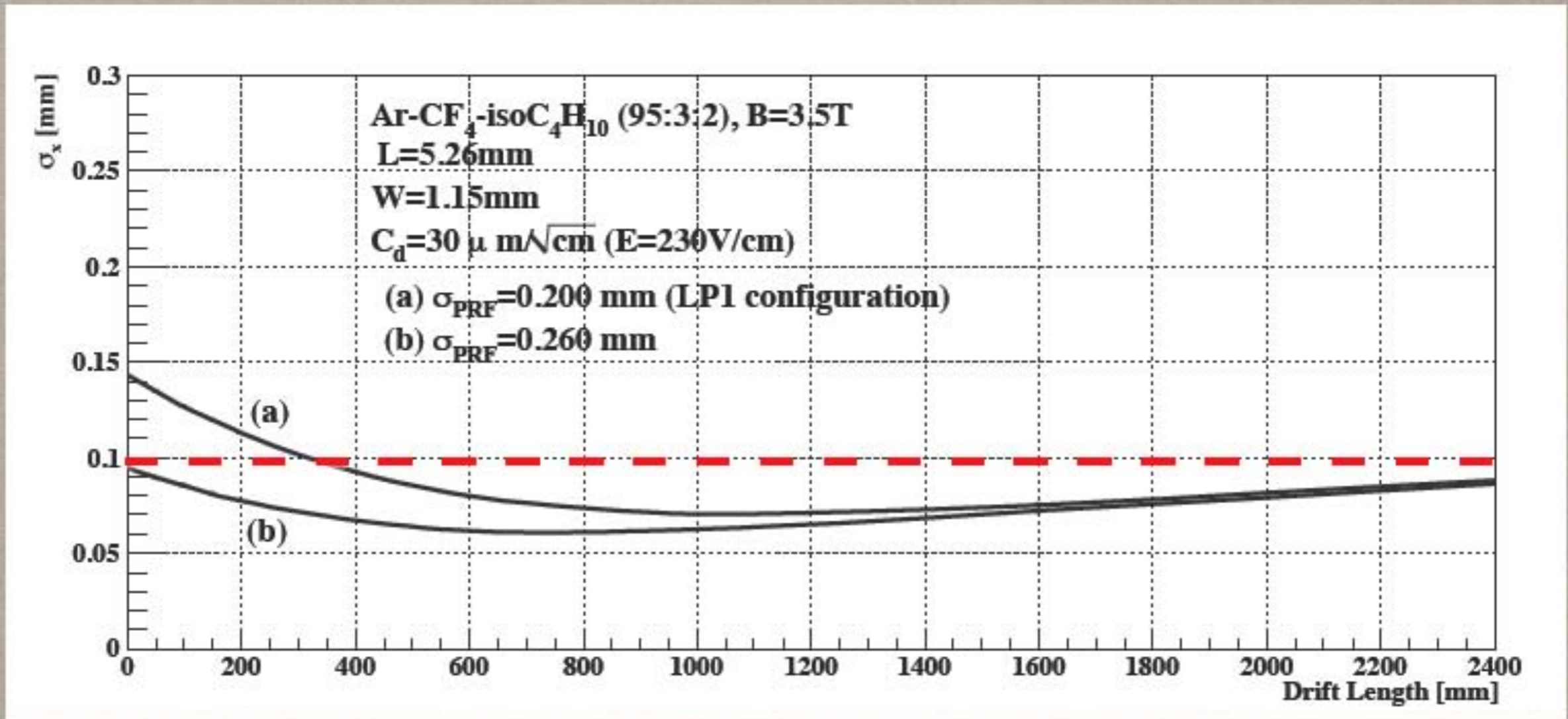
Pad size

We have a reason to choose 1mm pad width for GEM

Optimum pad width is 3~4 times of diffusion @ amp. region(PRF) in order to avoid hode scope effect



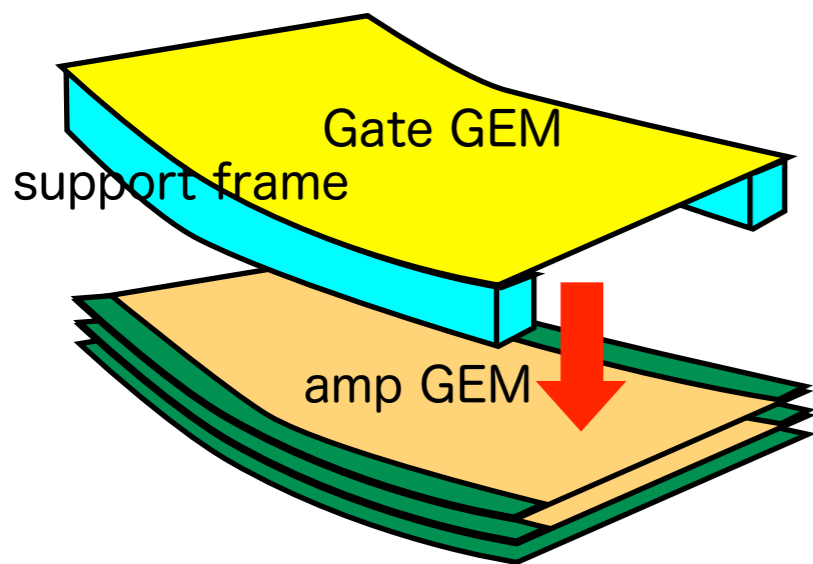
Extrapolation to the ILD-TPC



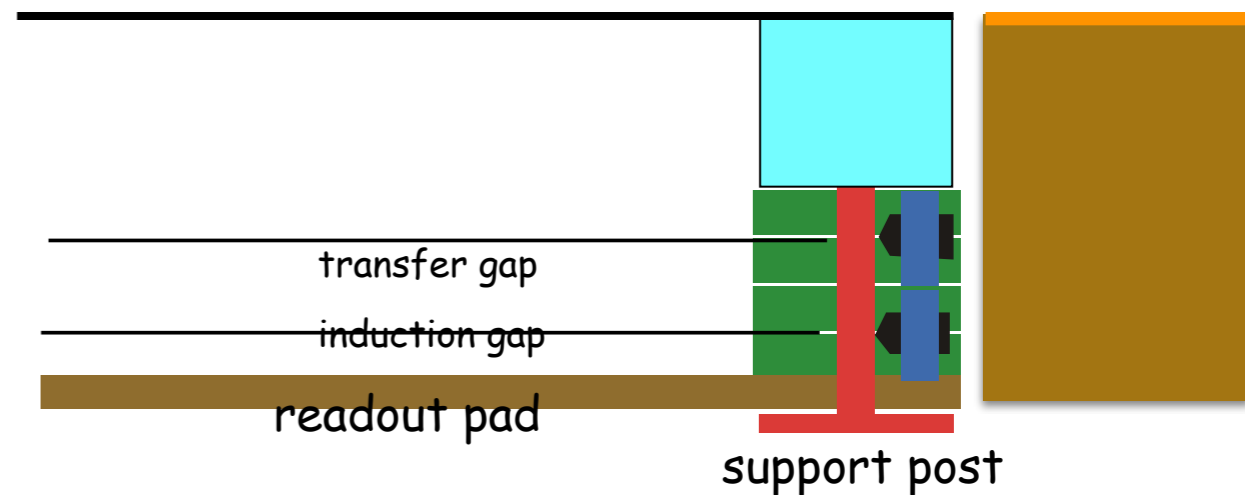
The expect performance is satisfied with the

In order to achieve 100um res. all over the drift volume, we have to have more diff. @amp region or narrower pad

GEM stretching method



14um Gate GEM



tension of GEM is applied against post

post metal

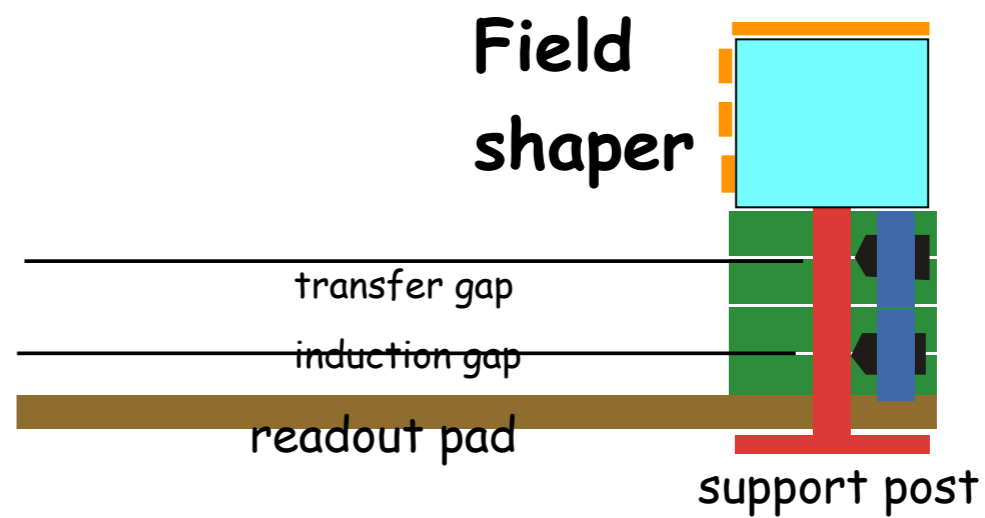
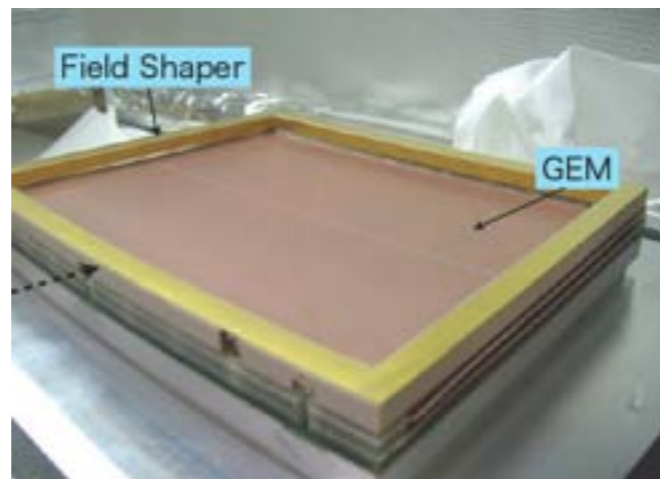
too much room for adjustment

difficult to align GEM on the place

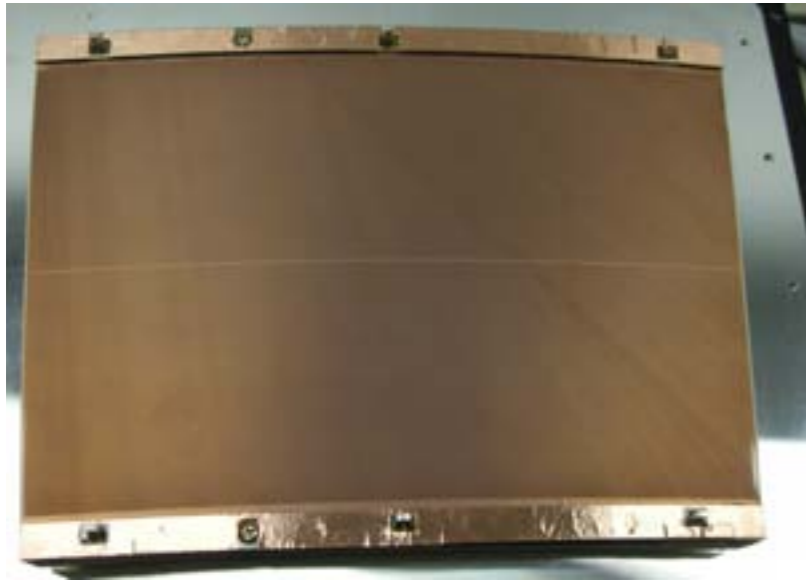
Gate GEM was not ready at the beginning

ugly structure(metal post, frame) distort E field

with side frame



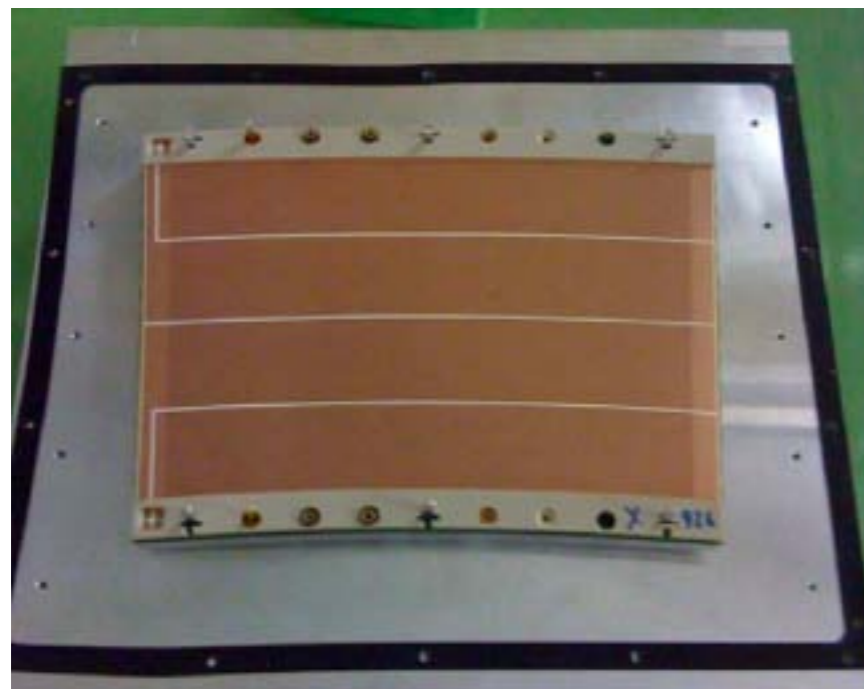
GEM sheet



segmentation 2

-> observe frequent trip
gap 300um

-> gap was too short
one segment trip -> discharge@gap

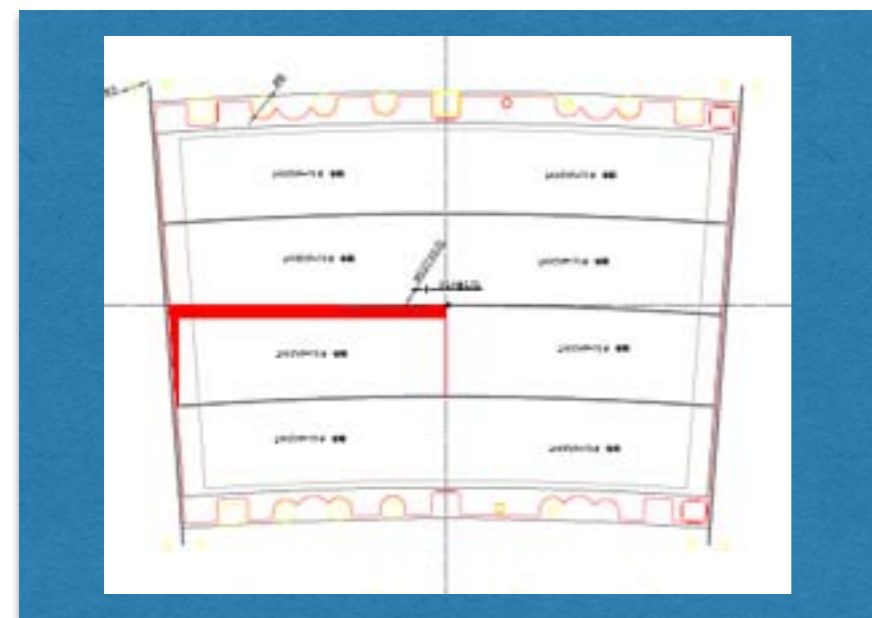


segmentation 4

-> improve? but many discharge
gap 1mm

-> HV OK but

-> this gap provide another distortion

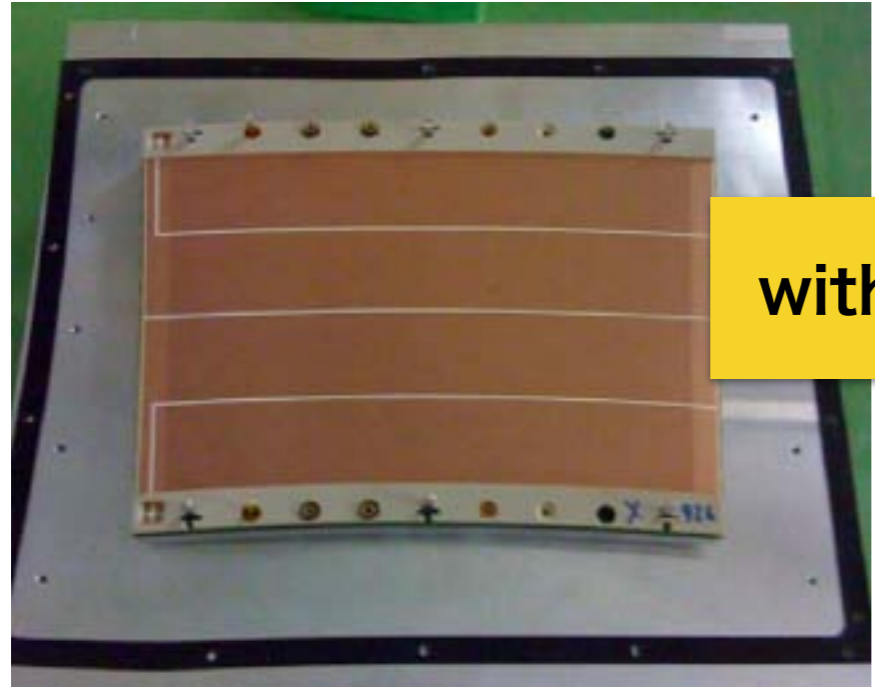
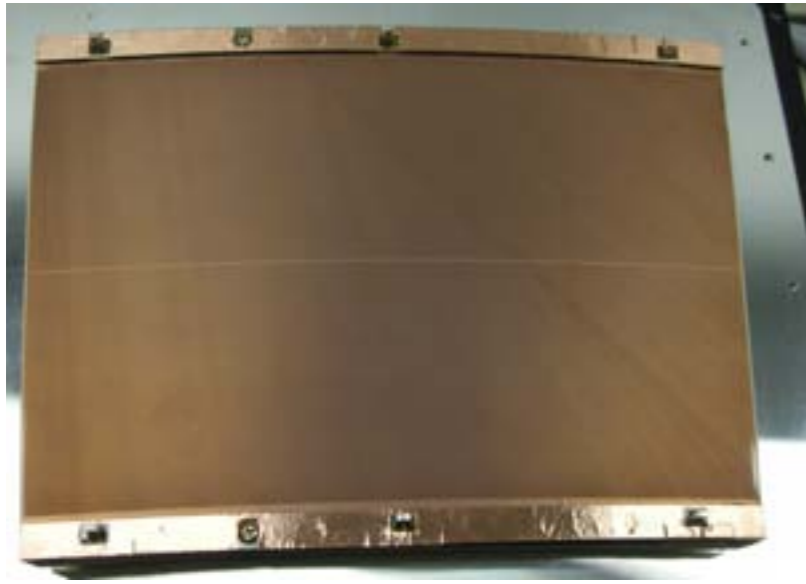


no segmentation@front/ 4 segments@back

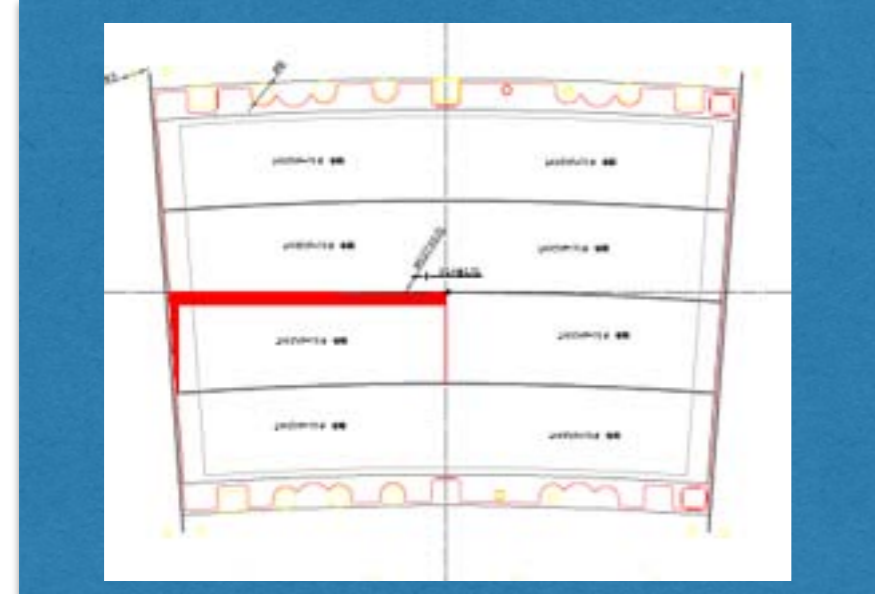
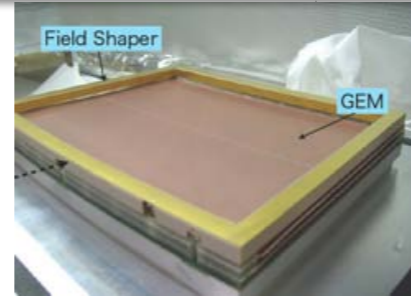
-> distortion became smaller

gap 500um

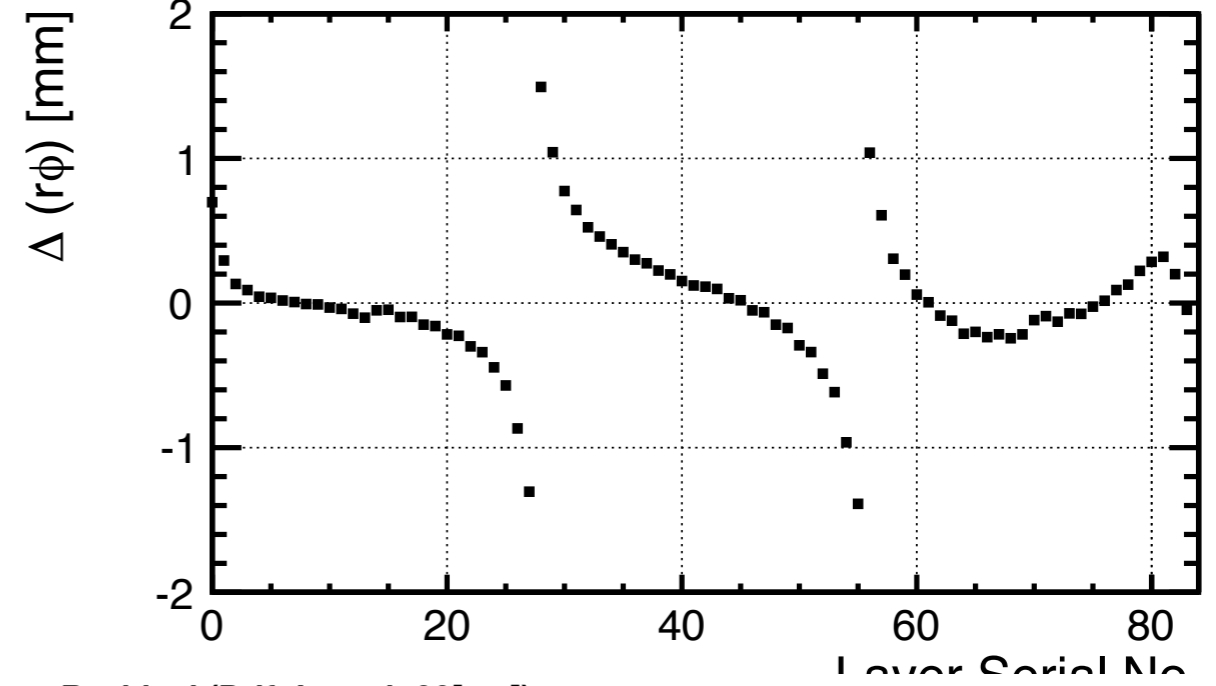
GEM sheet



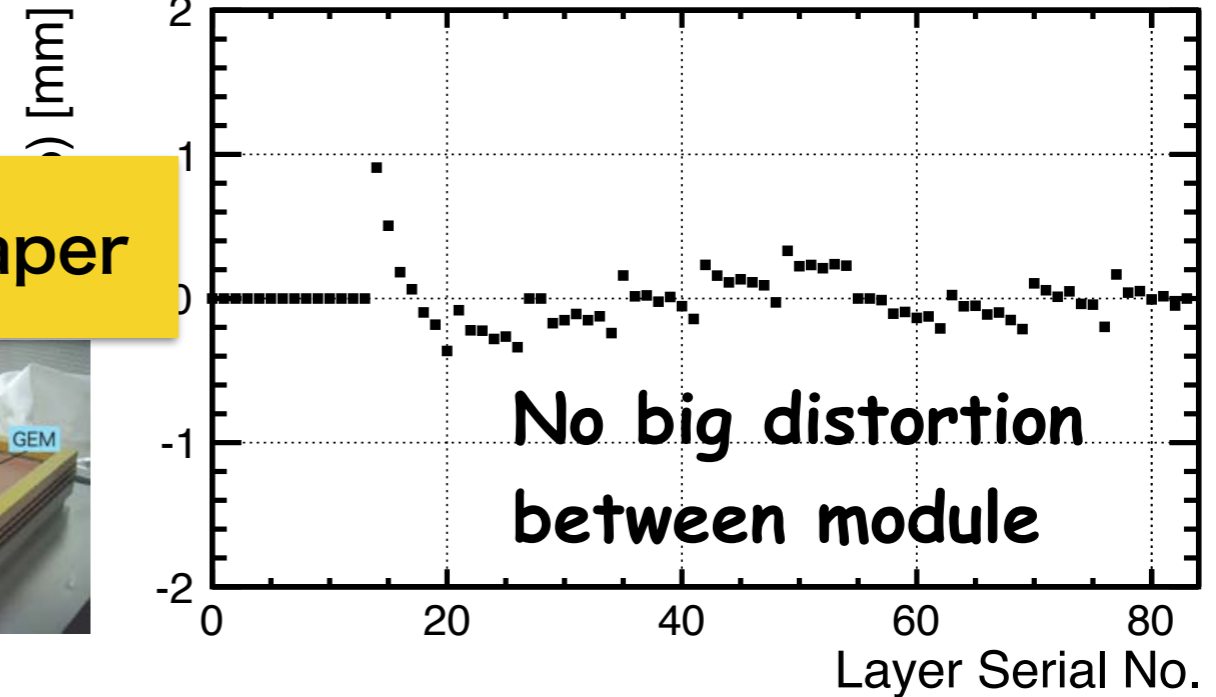
with field shaper



$r\phi$ Residual (Drift Length 19.2[cm])



$r\phi$ Residual (Drift Length 20[cm])



No big distortion between module

no segmentation
-> distortion
gap 500um

No Beam test

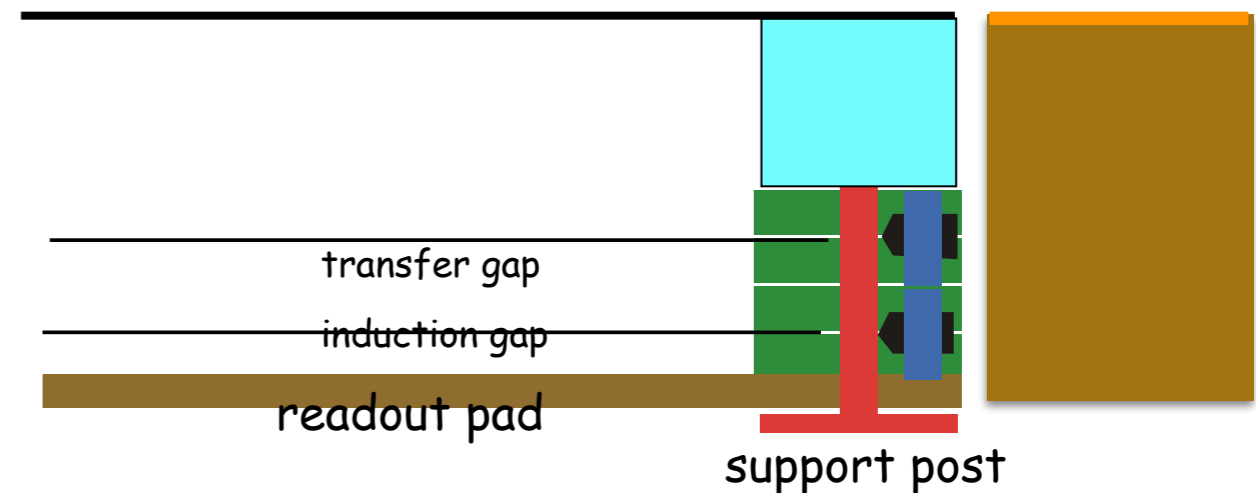
GEM discharge study

Micro discharge is counted during long term GEM operation for 50um(CERN, Raytech, Scienergy) and 100um(Scienergy) GEM
Result will be reported by Kato

no clear difference

Gate will be ready until Fall 2015

We can test the original configuration
Gate effect with beam track
transmission, distortion
distortion in module
distortion between modules



this module will be studied using Laser beam this year
No clear plan for DESY test beam (budget,..)

NEXT module

Upper structure

Gate GEM

GEM Amplification

how do we mount ?



PCB

Readable channel is
60% of LP1

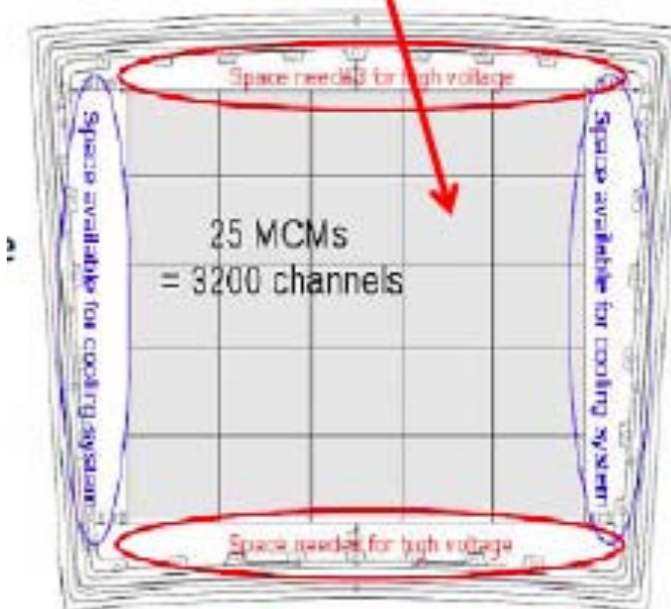
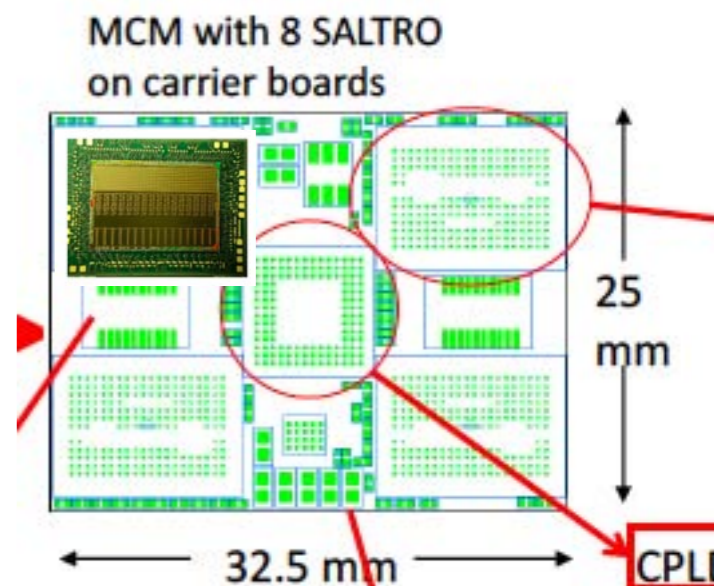
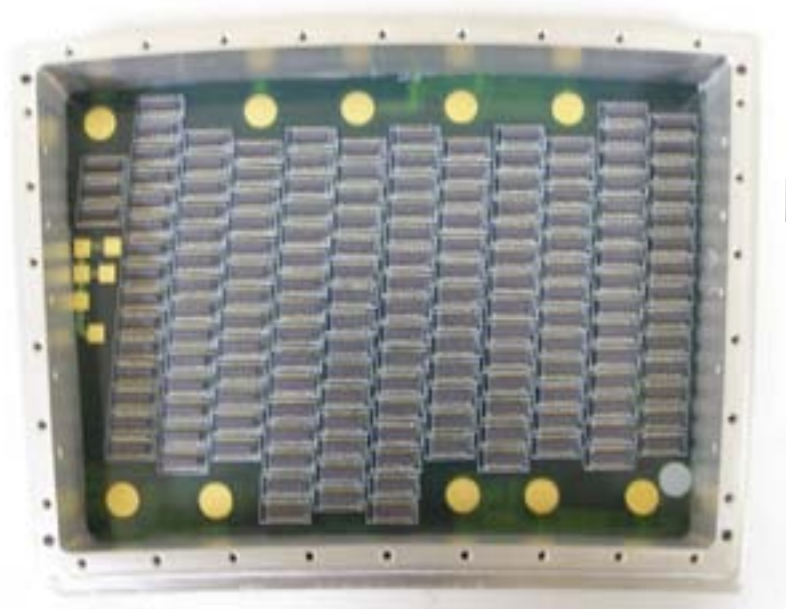
how do we read ?



Lower structure

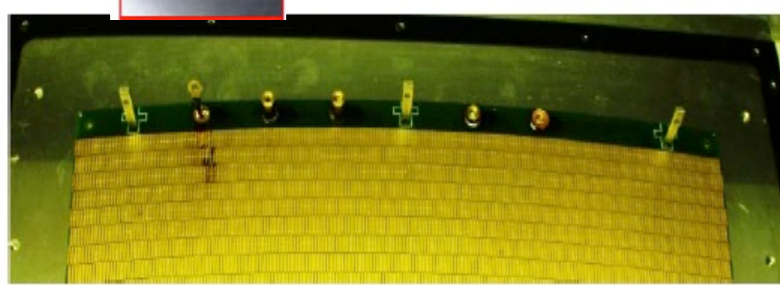
RO electronics/cooling/HV

how do we cool ?

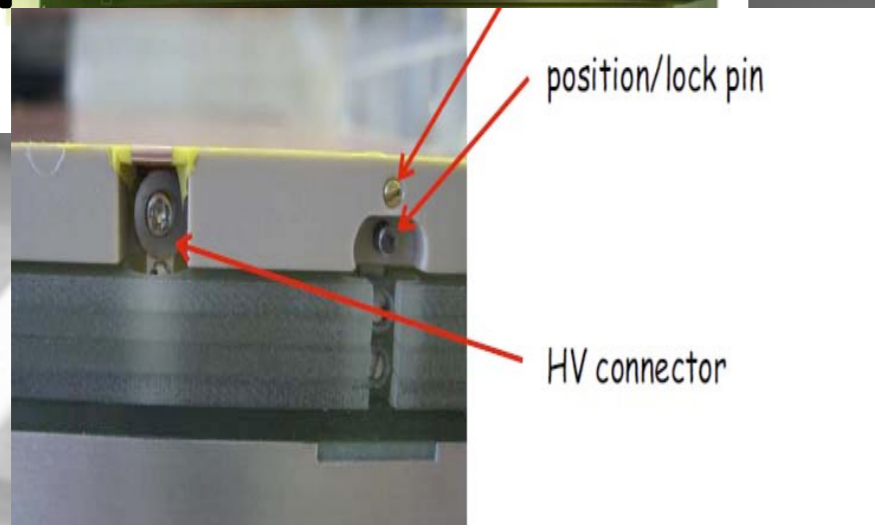
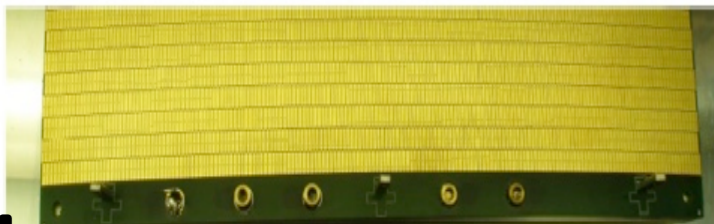


Upper structure

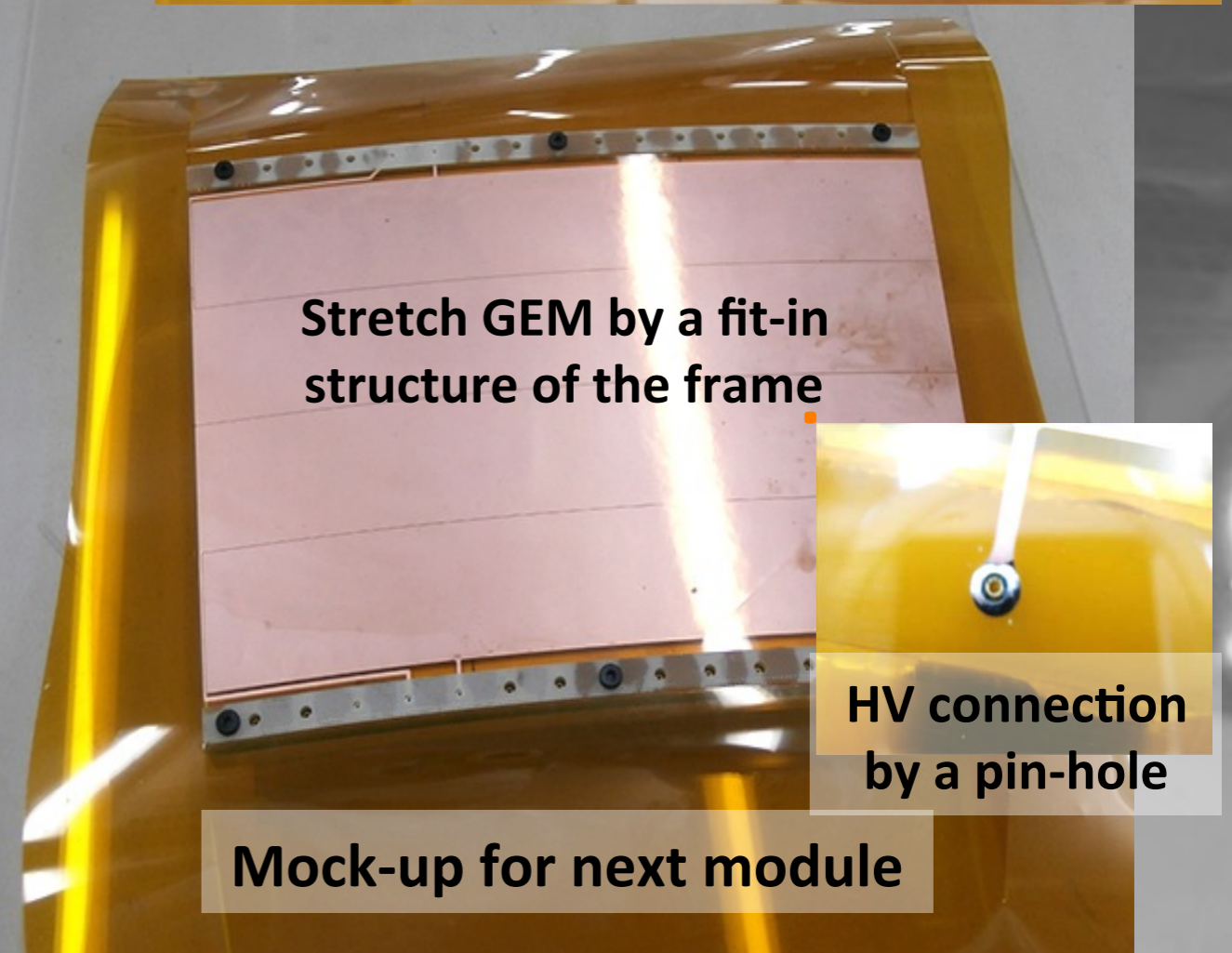
Different scheme is tested



The top side of the pad plane



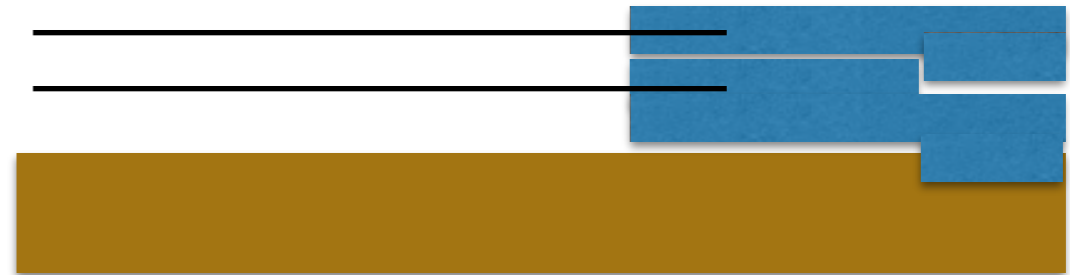
Current module



Upper structure

Fit-in structure

no room for adjustment
elasticity of GEM sheet



HV connection

pin and receptacle

Mockup is just delivered

We will check fabrication process / stability / replacability
HV connection stability....

amp. GEM structure 2 GEM or 3 GEM

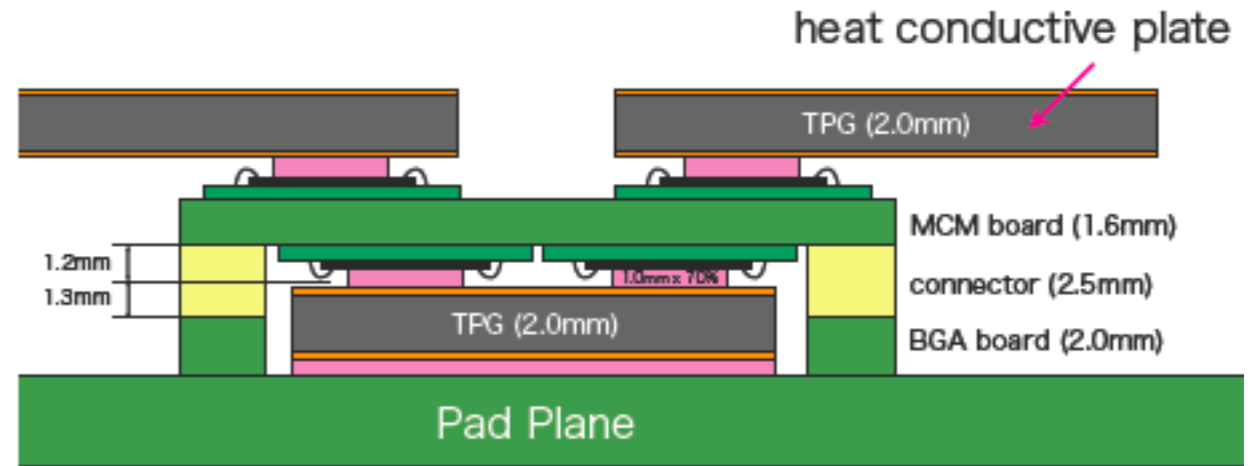
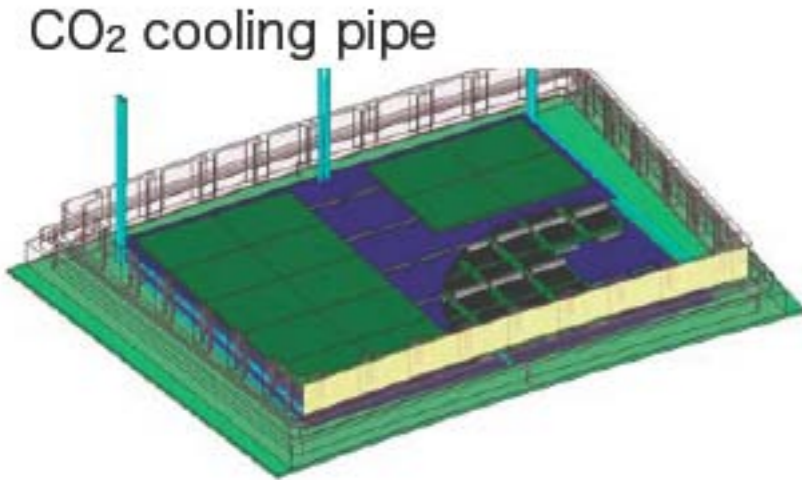
we couldn't establish advantage of 2 GEM (simpler ?)

How do we get more diffusion ? if we choose 1mm pad pitch
1cm Amp. region is acceptable ?

-> total 2cm thick structure above PCB ????

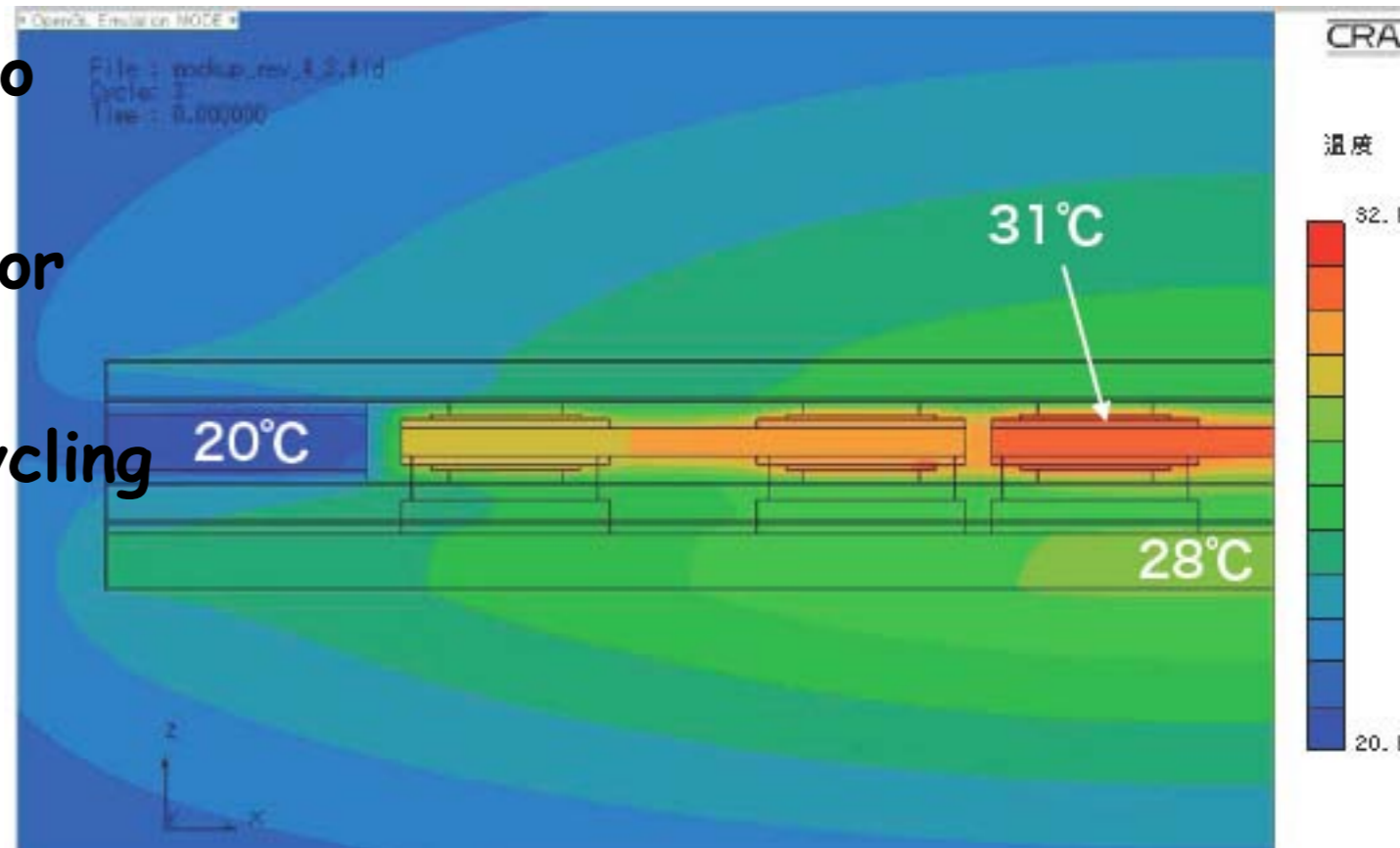
Lower structure

Readout electronics (Leif)



Cooling scheme is studied by Takahiro
simulation using TPG as heat conductor
non-negligible temp. gradient
w/o power cycling
heat flow through connector

Mockup study will be started



design of PCB toward next module

Not considered yet under 3200ch readout environment

It depends on how we set the goal of Next module

pad size is be kept and sensitive area is reduced

same width but 50% longer height and cover all area

20% larger pad in width&height cover all area

design of PCB is related to upper/lower structure

Upper structure must be considered through mockup study

Cooling scheme is also studied more

We may need at least 1 year to study these.

How do we fit into Common PCB plan ?

Unfortunately our budget of 2015 is very limited

What we can @2015 is

production of realistic GEM gate fit on the current module
test this module with laser facility

mockup study of upper structure
mockup study of cooling system

Summary

We have met real problems of module and learned many things
distortion related local module structure

GEM electrode gap : predictable and correctable

need more study for ExB effect

module gap : list. reduced by proper Field shaper op.

module gap distortion is correctable or not?

We still need to show advantage of our concept
minimize boundary effect

Test of new upper structure is on going.

Cooling is also considered using another mockup

These results will be integrated into next module design